

Chemicals available to UFNF Physics Users

- Isopropyl Alcohol
- Acetone
- Methanol
- DI water

- Developer: **AZ 300MIF** - 0.28 Normality – do not dilute.
Typical develop time 60-120 seconds (mild agitation recommended)

- Developer: **AZ 400K**
Concentrate
Mix 1:4(DI) for high contrast .28 N
Mix 1:3(DI) for high speed .35 N

Please Note: Shipley **MF319** Developer has been DISCONTINUED. Use **AZ 300MIF** in its place. The TMAH concentration is the same so no process changes should be needed.

- Microchem Remover PG (99% NMP, 1% surfactant)
- AZ 400T Stripper (72%NMP, 26% propylene glycol, 2% TMAH)
- MIBK:IPA 1:3 (Methyl Isobutyl Ketone, Isopropyl Alcohol)
- Microchem EBR PG (70-80% 1,3 Dioxolane , 20-30% PGME)

Contact UFNF Staff for help obtaining following chemicals, you will need your own labeled clean amber container:

- Positive Photoresist: **Shipley Microposit S1813**
PGMEA based, 1.3um@4000rpm, softbake-oven 105°C 30 min, softbake-hotplate 115°C, 80 sec
- Positive Photoresist: **AZ 9260**
PGMEA based, approx. 7.2 um@4000rpm, softbake 110°C, 80 sec
- PMMA: **Microchem Nano 950PMMA**
(viscosities = A2, A4, A6)
- Copolymer: **Microchem MMA (8.5) MAA** (8.5% methacrylic acid)
(Ethyl lactate based)